

| Ref # | Hits | Search Query   | DBs   | Default Operator | Plurals | Time Stamp       |
|-------|------|--|---|------------------|---------|------------------|
| L1    | 134  | ((wash\$4 or rins\$5) and (pure adj water) and (nozzle) and ((semiconductor or silicon or ("Si"))) adj substrate) and ((high adj molecular) or polymer or monomer)) and @ad<="20030912"                    | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR               | ON      | 2005/11/15 09:14 |
| L2    | 58   | 1 and spray  | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR               | ON      | 2005/11/15 09:14 |
| L3    | 78   | 1 and spray\$6   | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR               | ON      | 2005/11/15 09:15 |
| L4    | 25   | (wash\$4 or rins\$5) and ((semiconductor or silicon or ("Si"))) adj substrate) and (((behenic adj acid) or ("C.sub.27 H.sub.46 O")) or ((cholesterin) or ("C.sub.21 H.sub.43 COOH")))) and @ad<="20030912" | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR               | ON      | 2005/11/15 09:18 |
| L5    | 33   | ((wash\$5 or clean\$5) adj ((semiconductor or silicon or ("Si"))) adj substrate)) and (organic or polymer or monomer) and (boil\$4 adj point)  | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR               | ON      | 2005/11/15 09:22 |
| L6    | 10   | ((wash\$5 or clean\$5) adj ((semiconductor or silicon or ("Si"))) adj substrate)) and (organic or polymer or monomer) and (boil\$4 adj point) and ((temperature or heat) adj treat\$5)                     | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR               | ON      | 2005/11/15 09:22 |
| L7    | 29   | ((wash\$5 or clean\$5) adj ((semiconductor or silicon or ("Si"))) adj substrate)) and (organic or polymer or monomer) and (boil\$4 adj point) and @ad<="20030912"  | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR               | ON      | 2005/11/15 09:23 |
| L8    | 8    | ((wash\$5 or clean\$5) adj ((semiconductor or silicon or ("Si"))) adj substrate)) and (organic or polymer or monomer) and (boil\$4 adj point) and ((temperature or heat) adj treat\$5) and @ad<="20030912" | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR               | ON      | 2005/11/15 09:23 |

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| L9 | 890  | (438/758).CCLS.   | US-PGPUB;<br>USPAT;<br>USOCR;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR | OFF | 2005/11/15 09:49 |
| S1 | 2    | ((wash\$4 or rins\$5) with<br>((semiconductor or silicon or<br>("Si")) adj substrate) with (high<br>adj molecular)) and<br>@ad<="20030912"  | US-PGPUB;<br>USPAT;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB           | OR | ON  | 2005/04/05 10:34 |
| S2 | 16   | ((wash\$4 or rins\$5) same<br>((semiconductor or silicon or<br>("Si")) adj substrate) same (high<br>adj molecular)) and<br>@ad<="20030912"  | US-PGPUB;<br>USPAT;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB           | OR | ON  | 2005/04/05 10:42 |
| S3 | 692  | (wash\$4 or rins\$5) and<br>((semiconductor or silicon or<br>("Si")) adj substrate) and (high adj<br>molecular) and<br>@ad<="20030912"  | US-PGPUB;<br>USPAT;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB           | OR | ON  | 2005/04/05 10:42 |
| S4 | 22   | (wash\$4 or rins\$5) and<br>((semiconductor or silicon or<br>("Si")) adj substrate) and<br>((behenic adj acid) or<br>(cholesterin)) and<br>@ad<="20030912"  | US-PGPUB;<br>USPAT;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB           | OR | ON  | 2004/10/15 12:52 |
| S5 | 22   | (wash\$4 or rins\$5) and<br>((semiconductor or silicon or<br>("Si")) adj substrate) and<br>(((behenic adj acid) or ("C.sub.27<br>H.sub.46 O")) or ((cholesterin) or<br>("C.sub.21 H.sub.43 COOH")))) and<br>@ad<="20030912" | US-PGPUB;<br>USPAT;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB           | OR | ON  | 2005/11/15 09:18 |
| S6 | 2    | ("6165956").PN.   | US-PGPUB;<br>USPAT;<br>USOCR;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR | OFF | 2005/04/06 13:22 |
| S7 | 5119 | (wash\$4 or rins\$5 or clean\$6) and<br>((behenic adj acid) or<br>(cholesterin)) and<br>@ad<="20030912"   | US-PGPUB;<br>USPAT;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB           | OR | ON  | 2004/10/15 12:55 |
| S8 | 2    | ((wash\$4 or rins\$5 or clean\$6)<br>near (semiconductor)) and<br>((behenic adj acid) or<br>(cholesterin)) and<br>@ad<="20030912"   | US-PGPUB;<br>USPAT;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB           | OR | ON  | 2004/10/15 12:55 |

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| S9  | 22   | ((wash\$4 or rins\$5 or clean\$6) with (semiconductor)) and ((behenic adj acid) or (cholesterin)) and @ad<="20030912" | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON  | 2004/10/15 12:55 |
| S10 | 737  | ((wash\$4 or rins\$5 or clean\$6) and (semiconductor)) and ((behenic adj acid) or (cholesterin)) and @ad<="20030912"  | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON  | 2004/10/15 12:55 |
| S11 | 51   | ((wash\$4 or rins\$5 or clean\$6) same (semiconductor)) and ((behenic adj acid) or (cholesterin)) and @ad<="20030912" | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON  | 2004/10/15 13:11 |
| S12 | 4293 | ((wash\$4 or rins\$5 or clean\$6) and (semiconductor)) and (high adj molecular) and @ad<="20030912"                   | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON  | 2004/10/15 13:11 |
| S13 | 791  | ((wash\$4 or rins\$5 or clean\$6) same (semiconductor)) and (high adj molecular) and @ad<="20030912"                  | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON  | 2004/10/15 13:13 |
| S14 | 451  | ((wash\$4 or rins\$5 or clean\$6) with (semiconductor)) and (high adj molecular) and @ad<="20030912"                  | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON  | 2004/10/15 13:13 |
| S15 | 371  | ((wash\$4 or rins\$5 or clean\$6) near10 (semiconductor)) and (high adj molecular) and @ad<="20030912"                | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON  | 2004/10/15 13:13 |
| S16 | 10   | ((semiconductor or silicon) adj substrate) same ((organic adj molecule\$1) near3 layer)                               | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON  | 2004/11/05 14:07 |
| S17 | 3    | ((("20030171239") or ("6689473") or ("5970381"))).PN.   | US-PGPUB; USPAT; USOCR                      | OR | OFF | 2005/02/22 14:05 |

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| S18 | 30 | ((("4722906") or ("4826759") or ("4973493") or ("4979959") or ("5002582") or ("5073484") or ("5217492") or ("5258041") or ("5263992") or ("5414075") or ("5512329") or ("5512474") or ("5563056") or ("5637460") or ("5654162") or ("5707818") or ("5714360") or ("5741551") or ("5744515") or ("5783502") or ("5858653") or ("5942555") or ("5981298") or ("6007833") or ("6020147") or ("6077698") or ("6090995") or ("6121027") or ("6156345") or ("6214901"))).PN. | US-PGPUB;<br>USPAT;<br>USOCR                                      | OR | OFF | 2004/11/05 14:22 |
| S19 | 2  | ("20020158256").PN.  | US-PGPUB;<br>USPAT;<br>USOCR;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR | OFF | 2004/08/30 09:47 |
| S21 | 2  | ("20010005601").PN.  | US-PGPUB;<br>USPAT;<br>USOCR;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR | OFF | 2004/08/30 12:57 |
| S22 | 2  | ("6294406").PN.  | US-PGPUB;<br>USPAT;<br>USOCR;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR | OFF | 2004/08/30 12:57 |
| S23 | 8  | ((("6762078") or ("6395578") or ("6515356") or ("6501184"))).PN.   | US-PGPUB;<br>USPAT;<br>USOCR;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR | OFF | 2004/08/30 13:12 |
| S29 | 2  | ("6294406").PN.  | US-PGPUB;<br>USPAT;<br>USOCR;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR | OFF | 2004/08/30 13:30 |
| S30 | 2  | ("6531350").PN.  | US-PGPUB;<br>USPAT;<br>USOCR;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR | OFF | 2004/08/30 13:30 |

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| S32 | 5   | gate and source and drain and (light adj dop\$6) and ((deep or depth) adj dop\$6) and silicide and plug  | US-PGPUB;<br>USPAT;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB           | OR | ON  | 2004/08/30 13:38 |
| S35 | 4   | ((("5918130") or ("6087235")).PN.  | US-PGPUB;<br>USPAT;<br>USOCR;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR | OFF | 2004/08/30 13:44 |
| S52 | 61  | gate and source and drain and (light\$3 adj dop\$6) and ((depth or deep or expand\$5) adj dop\$6) and (plug)   | US-PGPUB;<br>USPAT;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB           | OR | ON  | 2004/08/30 14:02 |
| S53 | 50  | gate and source and drain and (light\$3 adj dop\$6) and ((depth or deep or expand\$5) adj dop\$6) and silicide and (plug)                              | US-PGPUB;<br>USPAT;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB           | OR | ON  | 2004/08/30 14:31 |
| S77 | 2   | ("5427964").PN.  | US-PGPUB;<br>USPAT;<br>USOCR;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR | OFF | 2005/04/07 14:15 |
| S83 | 2   | ((("5932493") or ("6165956")).PN.  | US-PGPUB;<br>USPAT;<br>USOCR                                      | OR | OFF | 2005/04/06 14:44 |
| S84 | 802 | (438/758).CCLS.  | US-PGPUB;<br>USPAT;<br>USOCR;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB | OR | OFF | 2005/11/15 09:49 |
| S85 | 751 | (wash\$4 or rins\$5) and ((semiconductor or silicon or ("Si")) adj substrate) and (high adj molecular) and @ad<="20030912"                             | US-PGPUB;<br>USPAT;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB           | OR | ON  | 2005/04/05 10:42 |
| S87 | 21  | ((wash\$4 or rins\$5) with ((semiconductor or silicon or ("Si")) adj substrate) with ((high adj molecular) or polymer or monomer)) and @ad<="20030912" | US-PGPUB;<br>USPAT;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB           | OR | ON  | 2005/04/05 10:43 |

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| S88 | 1   | ((wash\$4 or rins\$5) same (pure adj water) same (nozzle) same ((semiconductor or silicon or ("Si"))) adj substrate) same ((high adj molecular) or polymer or monomer)) and @ad<="20030912"               | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/04/06 13:25 |
| S89 | 1   | ((wash\$4 or rins\$5) same ((pure or purif\$6) adj water) same (nozzle) same ((semiconductor or silicon or ("Si"))) adj substrate) same ((high adj molecular) or polymer or monomer)) and @ad<="20030912" | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/04/06 13:15 |
| S90 | 155 | ((wash\$4 or rins\$5) same ((semiconductor or silicon or ("Si"))) adj substrate) same ((high adj molecular) or polymer or monomer)) and @ad<="20030912"   | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/04/06 13:18 |
| S91 | 1   | ((wash\$4 or rins\$5) same (water) same (nozzle) same ((semiconductor or silicon or ("Si"))) adj substrate) same ((high adj molecular) or polymer or monomer)) and @ad<="20030912"                        | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/04/06 13:25 |
| S92 | 130 | ((wash\$4 or rins\$5) and (pure adj water) and (nozzle) and ((semiconductor or silicon or ("Si"))) adj substrate) and ((high adj molecular) or polymer or monomer)) and @ad<="20030912"                   | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/11/15 09:14 |
| S93 | 54  | S92 and spray   | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/11/15 09:14 |
| S94 | 74  | S92 and spray\$6  | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/11/15 09:15 |